



Correct as of 05-Feb-2025 11:56am For the latest version of our agenda, visit csinternational.net

Day 1 - Monday 7th April 2025

18:30 Pre-conference networking drinks reception

Day 2 - Tuesday 8th April 2025

08:00 Registration and welcome refreshments 08:50 Housekeeping by Chris Meadows and Tim Bettles - Conference Chairs Expanding the emission envelope Expanding the Spectral Range of GaN-based SLEDs 09:00 Presented by Marco Malinverni - Exalos Perfecting GaN VCSEL Production Process 09:15 Presented by Tetsuya Takeuchi - Meijo University Connected Metrology for Growth and Characterization of InP and GaAs Laser Structures - from Epi to Etch 09:30 Presented by Iris Claussen - LayTec Presentation by Umicore 09:45 Presented by Name to be advised - Umicore Presentation by Vertilas 10:00 Presented by Christian Neumeyr - Vertilas The Power of Pseudomorphic Nitrides 10:15 Presented by Leo Schowalter - Lit Thinking 10:30 Morning Break GaN: Going beyond fast charging Achieving Avalanche in GaN-on-silicon Diodes 11:10 Presented by Farid Medjdoub - University of Lille Presentation by Semilab 11:25 Presented by Name to be advised - Semilab Advancements in X-ray Metrology for GaN and Compound Semiconductors 11:40 Presented by Assunta Vigliante - Rigaku AIXTRON Leading Epitaxy Solutions for High Volume Manufacturing of GaN-based Power Devices 11:55 Presented by Dr. Nicolas Muesgens - Aixtron Enhancing Analytical Accuracy of Active Epilayers in Compound Semiconductors by Multi-ion Species Plasma-FIB and Novel 12:10 STEM Techniques Presented by Antonio Mani - Thermo Fisher Scientific Presentation by Yole Group 12:25 Presented by Ezgi Dogmus - Yole Group 12:40 Lunch Break Harnessing the Underestimated Potential of GaN in the Digitalization Revolution: A Catalyst for Unforeseen Innovation in 14:10 **Energy Efficiency** Presented by Roberto Crisafulli - STMicroelectronics Epitaxial GaN Growth using MBE for the Development of Next-Generation Devices 14:25 Presented by Romain Bruder - Riber Presentation by Raith 14:40 Presented by Amanda Wscieklica - Raith Presentation by Veeco 14:55 Presented by Name to be advised - Veeco Advancement in X-Ray Metrology for GaN Power Device Ramp Up 15:10 Presented by Qian Zheng - Bruker 15:25 Afternoon Break Maintaining momentum for the microLED Perfecting the Polychromatic Pixel 16:05 Presented by Michelle Chen - Q-Pixel Inc MicroSolid Printing: Redefining the Future of MicroLED Displays 16:20 Presented by Reza Chaji - Vue Real Leveraging NIL for ILED Lens Packaging 16:35 Presented by Thomas Achleitner - EV Group Presentation by Yole Group 16:50 Presented by Raphaël Mermet-Lyaudoz - Yole Group Pioneering Mass Production and Commercialisation of MicroLED Microdisplays for AR 17:05 Presented by Kunal Kashyap - Porotech Revolutionising microLED Displays with Nanowires 17:20 Presented by Pierre Tchoulfian - Aledia

17:35 Closing Remarks

18:30 Networking Drinks / Dinner Reception

Day 3 - Wednesday 9th April 2025

The promise of cubic Boron Nitride (c-BN)

Presented by Siddha Pimputkar - Lehigh University

Presented by Name to be advised - Fraunhofer IAF

Closing Remarks

14:40

14:55

15:10

08:00 Registration and welcome refreshments 08:50 Housekeeping by Chris Meadows and Tim Bettles - Conference Chairs **Optimising opportunities for SiC success** The Merits of the Merged p-i-n SiC Schottky Diode 09:00 Presented by Llewellyn Vaughan-Edmunds - Navitas **Presentation by Applied Materials** 09:15 Presented by Name to be advised - Applied Materials Integrated Metal Etch and Photoresist Strip Solution for SiC Manufacturing 09:30 Presented by Bernhard Hammerl - Siconnex Customized Solutions GmbH 09:45 Presentation by Onto Innovation Presentation by SCREEN 10:00 Presented by Alessandro Rossi - SCREEN SPE 10:15 Morning Break Presentation by Nanotronics 10:55 Presented by Name to be advised - Nanotronics **PVA TePla Metrology Solutions for Compound Semiconductors** 11:10 Presented by Name to be advised - PVA TePla AG How Artificial Intelligence Heralds the New Era of Wafering 11:25 Presented by Malte Mueller - Lapmaster Wolters Crystal Orientation for Optimizing Quality and Yield throughout the Process Chain 11:40 Presented by Name to be advised - Malvern Panalytical Presentation by Kellenberger 11:55 Presented by Jeff Gum - Kellenberger Ultra-wide bandgap materials: The ultimate devices Sponsored by Precision Fabricators 12:10 Lunch Break Prospects of (ultra) Wide Bandgap Oxide ICs 13:40 Presented by Xiaohang Li - KAUST A Solution to Doping AlN Enabling a New Era of Nitride Semiconductors 13:55 Presented by Alan Doolittle - Georgia Institute of Technology Electric Field Engineering to Unlock the Potential of Gallium Oxide Power Devices 14:10 Presented by Nolan Hendricks - AFRL (Air Force Research Laboratory) Efficient Diameter Enlargement of Bulk AlN 14:25 Presented by Carsten Hartmann - Leibniz-Institut für Kristallzüchtung (IKZ)

Expanding the Ultra-Wide Bandgap Portfolio with Transition Metal Nitrides: AlScN and AlYN



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